Kenta Suzuki

List of Publications by Year
in descending order

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Version: 2024-02-01

37 papers	163 citations	1307594 7 h-index	1281871 11 g-index
37 all docs	37 docs citations	37 times ranked	72 citing authors

#	Article	IF	Citations
1	Fabrication of high-aspect-ratio micropatterns in soluble block-copolymer polyimides by a UV-assisted thermal imprint process. Journal of Mechanical Science and Technology, 2019, 33, 3755-3760.	1.5	0
2	Mold Design and Process for Application of Nanoimprint Lithography to Interconnections. Journal of Japan Institute of Electronics Packaging, 2019, 22, 158-163.	0.1	0
3	Solubility Property of Condensable Gases of Trans-1-Chloro-3,3,3-Trifluoropropene and Trans-1,3,3,3-Tetrafluoropropene in UV Nanoimprint. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2019, 32, 123-130.	0.3	2
4	Evaluation of Nanoimprinting Multilayer Lift-off Process using Spin-on-glass for Nanogap Electrode Array. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2018, 31, 277-282.	0.3	1
5	Filling Behavior and Mold Release Force in UV Nanoimprinting Using PDMS Mold in Different Atmosphere. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2018, 31, 295-300.	0.3	6
6	Chip-scale pattern modification method for equalizing residual layer thickness in nanoimprint lithography. Japanese Journal of Applied Physics, 2018, 57, 06HG03.	1.5	3
7	Pt Nanogap Electrode Fabrication by Two-Layer Lift-Off UV-NIL and Nanowire Breakdown. IEEE Nanotechnology Magazine, 2018, 17, 1094-1097.	2.0	2
8	Basic Verification of Method for Automated Design of Capacity-Equalized Mold for Nanoimprint Lithography. Journal of Nanoscience and Nanotechnology, 2017, 17, 8475-8479.	0.9	1
9	Bubble-free patterning with low line edge roughness by ultraviolet nanoimprinting using trans-1,3,3,3-tetrafluoropropene condensable gas. Applied Physics Letters, 2016, 109, .	3.3	10
10	Ultraviolet Nanoimprint Lithography in the Mixture of Condensable Gases with Different Vapor Pressures. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2016, 29, 181-187.	0.3	4
11	Bubble-free high-speed UV nanoimprint lithography using condensable gas with very low global warming potential. Japanese Journal of Applied Physics, 2016, 55, 076502.	1.5	6
12	Selective Cu Patterning on Polyimide Using UV Surface Treatment and Electroless Plating. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2015, 28, 157-161.	0.3	3
13	Resin filling of UV-cured nanoimprints using pentafluoropropane to fabricate large patterns with a thin residual layer. Microelectronic Engineering, 2015, 136, 81-84.	2.4	1
14	Nano-patterning on soluble block copolymer polyimide by nanoimprint. Japanese Journal of Applied Physics, 2015, 54, 088002.	1.5	4
15	Simple fabrication process for UV nanoimprint mold with embedded metal alignment marks for in-liquid alignment. Japanese Journal of Applied Physics, 2014, 53, 06JK01.	1.5	3
16	Cu/Polyimide Multilayer Interconnections Fabricated by Nanoimprint at Every Lithography Process. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2014, 27, 73-80.	0.3	4
17	Fabrication of sub 20-nm wide grooves in a quartz mold by space narrowing dry etching. Microelectronic Engineering, 2013, 110, 432-435.	2.4	4
18	Improved Performances of All-Polyimide Fluidic Devices Using Thermal Nanoimprinting. Applied Mechanics and Materials, 2013, 300-301, 1360-1363.	0.2	0

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19	Control of Resin Filling and Pattern Quality of Ultraviolet Nanoimprint Lithography in Pentafluoropropane and Helium Ambient. Japanese Journal of Applied Physics, 2013, 52, 06GJ07.	1.5	7
20	Uniform Residual Layer Creation in Ultraviolet Nanoimprint Using Spin Coat Films for Sub-100-nm Patterns with Various Pattern Densities. Japanese Journal of Applied Physics, 2013, 52, 06GJ06.	1.5	5
21	Effective Linewidth Measurement of 45-nm-Half-Pitch Ultraviolet Nanoimprint Lithography Patterns by Scanning Electron Microscope Inspection and Extremely Shallow Si Etching. Japanese Journal of Applied Physics, 2012, 51, 06FJ09.	1.5	1
22	Throughput of Ultraviolet Nanoimprint in Pentafluoropropane Using Spin Coat Films under Thin Residual Layer Conditions. Japanese Journal of Applied Physics, 2012, 51, 06FJ10.	1.5	9
23	In-situEvaluation of Air/Oxygen Percentage Variation by Introducing 1,1,1,3,3-Pentafluoropropane in Ultraviolet Nanoimprint Lithography. Japanese Journal of Applied Physics, 2012, 51, 118002.	1.5	4
24	Transfer of Relatively Large Microstructures on Polyimide Films using Thermal Nanoimprinting. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2012, 25, 255-260.	0.3	9
25	Real-time full-area monitoring of the filling process in molds for UV nanoimprint lithography using dark field illumination. Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics, 2012, 30, 06FB13.	1.2	3
26	Effective Linewidth Measurement of 45-nm-Half-Pitch Ultraviolet Nanoimprint Lithography Patterns by Scanning Electron Microscope Inspection and Extremely Shallow Si Etching. Japanese Journal of Applied Physics, 2012, 51, 06FJ09.	1.5	8
27	Throughput of Ultraviolet Nanoimprint in Pentafluoropropane Using Spin Coat Films under Thin Residual Layer Conditions. Japanese Journal of Applied Physics, 2012, 51, 06FJ10.	1.5	4
28	In-situEvaluation of Air/Oxygen Percentage Variation by Introducing 1,1,1,3,3-Pentafluoropropane in Ultraviolet Nanoimprint Lithography. Japanese Journal of Applied Physics, 2012, 51, 118002.	1.5	7
29	Fabrication Processes for Capacity-Equalized Mold with Fine Patterns. Japanese Journal of Applied Physics, 2011, 50, 06GK04.	1.5	1
30	Effects of Granularity of Complementary Patterns in a Capacity-Equalized Mold Used for UV Nanoimprint Lithography. Japanese Journal of Applied Physics, 2011, 50, 06GK08.	1.5	2
31	Study on Quartz Multitier Mold Fabrication Using Gray Scale Laser Beam Lithography. Japanese Journal of Applied Physics, 2011, 50, 06GK03.	1.5	1
32	Study on Change in UV Nanoimprint Pattern by Altering Shrinkage of UV Curable Resin. Japanese Journal of Applied Physics, 2011, 50, 06GK09.	1.5	13
33	Flexible Polyimide Micropump Fabricated Using Hot Embossing. Japanese Journal of Applied Physics, 2011, 50, 06GM09.	1.5	16
34	Flexible Polyimide Micropump Fabricated Using Hot Embossing. Japanese Journal of Applied Physics, 2011, 50, 06GM09.	1.5	15
35	Freely Expandable Single Crystalline Si Networks for MEMS Applications. IEEJ Transactions on Sensors and Micromachines, 2010, 130, 130-134.	0.1	1
36	MEMS Tilt Sensor Fabricated Utilizing Anodic Bonding of Thin Silicon Film on Glass Substrate. IEEJ Transactions on Sensors and Micromachines, 2009, 129, 328-332.	0.1	1

#	Article	IF	Citations
37	Ring-Shaped Silicon Resonator Using (2,1) In-Plane Resonance Mode. Applied Mechanics and Materials, 0, 189, 274-280.	0.2	2